



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Lamotte et al.

Application No. 09/891,649

Filed: June 26, 2001

For: MATERIAL AND METHOD FOR

MAKING AN ELECTROCONDUCTIVE

PATTERN

Art Unit:

1752

Examiner:

John S Y Chu

APR 0 8 7003

AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Dear Sir:

In response to the Office Action dated December 18, 2002, please enter the following amendments and consider the following remarks.

AMENDMENTS

IN THE CLAIMS:

Please add the following new claims:

18. (New) A material for making an electroconductive pattern, said material comprising a support and a light-exposure differentiable element, characterized in that said light-exposure differentiable element comprises an outermost layer containing a polyanion and a polymer or copolymer of a substituted or unsubstituted thiophene, and optionally a second layer contiguous with said outermost layer; and wherein said outermost layer and/or said optional second layer contains a light-sensitive component capable upon exposure of changing the removability of the exposed parts of said outermost layer relative to the unexposed parts of said outermost layer, said light-sensitive compound selected from the group consisting of a multidiazonium salt, a resin comprising a diazonium salt and a quinonediazide compound.

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